2D nitrides

The Nobel Prize awarded to Nakamura acknowledged that bulk group-III nitrides like GaN, AlN and InN are important materials. They are used for a very wide range of applications such as solid-state lighting, LED, laser and photovoltaics [1].

Two-dimensional materials such as III-Nitrides (III-N) have been making a fuss in the material science field lately because of their unique physico-chemical properties and rare physical phenomena, that might allow electronics to be smaller. Experimentally, scientists successfully were able to grow AlN and GaN sheets by epitaxy growth techniques on transferred graphene Si substrates [2], but for 2D InN, its realization hasn’t seen light yet.

Physical Properties of 2D Nitrides

Monolayered AlN, InN and GaN nano sheets have flat honeycomb structure of 2D nitrides is similar to that of graphene, but with polar bonds owing to the distinct electronegativity of the lattice atoms.

For 2D AlN InN and GaN, Gap energy increases when applied strain is compressive strain applied, and decreases when strain applied is tensile. With AlN gap remains indirect and shifts from direct to indirect at 2% of strain for InN and shift from indirect to direct at -4% of strain for GaN.

Computational methods

Our first-principles calculations are based on DFT using the Quantum Espresso package and the pseudo-potential method and ultra-soft pseudopotentials. The exchange-correlation potential is approximated the Perdew–Burke–Ernzerhof approximation (PBE) and the Heyd-Scuseria-Ernzerhof hybrid (HSE06) for the electronic structure calculation. The plane wave basis set was defined by energy cut-off at 40 Ry and a 12x12x1 k-point grid in the first-Brillouin zone for all the previous 2D materials. To exclude interactions between neighbor slabs, we used a 15 Å vacuum space in the z direction perpendicular to the monolayer surface.

Effect of strain on the electronic structure

Among many techniques such as doping, chemical functionalization, biaxial strain also can be effective to tailor the electronic properties and energy band structure of a 2D semiconductor. The strain results in a displacement of both the conduction and valence bands, leading to the variation of the primary band gap which is the main interest to fabricate under-strain operation devices. A biaxial compressive and tensile strain from -6% to 6% was applied on the structures affecting their energy band structures, band gaps, effective masses.

Effect of strain on the electronic structure

<table>
<thead>
<tr>
<th>Compound</th>
<th>Lattice parameter (Å)</th>
<th>Band gap (eV)</th>
<th>Effective mass (m^*</th>
<th>Charge</th>
</tr>
</thead>
<tbody>
<tr>
<td>AlN</td>
<td>3.123</td>
<td>3.212</td>
<td>0.446</td>
<td>1.731</td>
</tr>
<tr>
<td>InN</td>
<td>3.113</td>
<td>3.19</td>
<td>3.616</td>
<td>1.731</td>
</tr>
<tr>
<td>GaN</td>
<td>3.113</td>
<td>3.19</td>
<td>3.616</td>
<td>1.731</td>
</tr>
</tbody>
</table>

Variation of the electron effective mass with applied stress

The effective mass and of AlN, InN and GaN can be tuned effectively by different strain % When the structures are under a compressive strain, we notice the increase of the effective mass of electron and the decrease of the effective mass of hole for all the compounds.

When the structures are under a tensile strain, we notice the decrease of the effective mass of electron and the increase of for all the compounds.

Change in emissio spectra

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References